

Figure 1: Cross Sectional View of Single Hardmask Structure

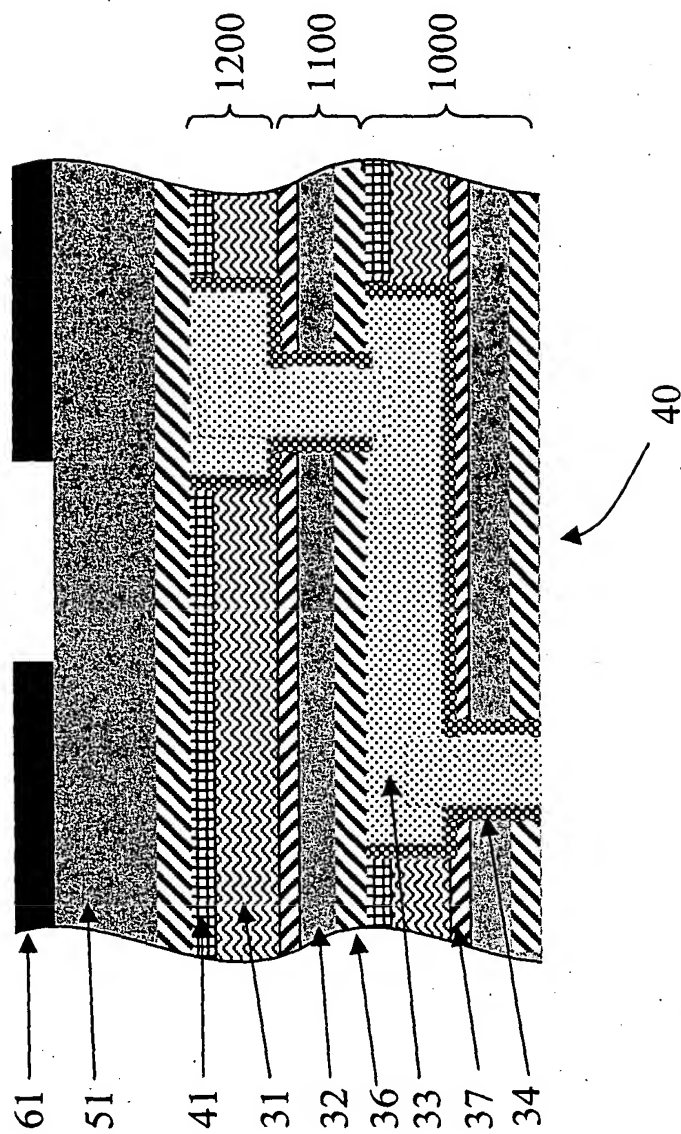


Figure 2: Cross Sectional View of Clustered Hardmask

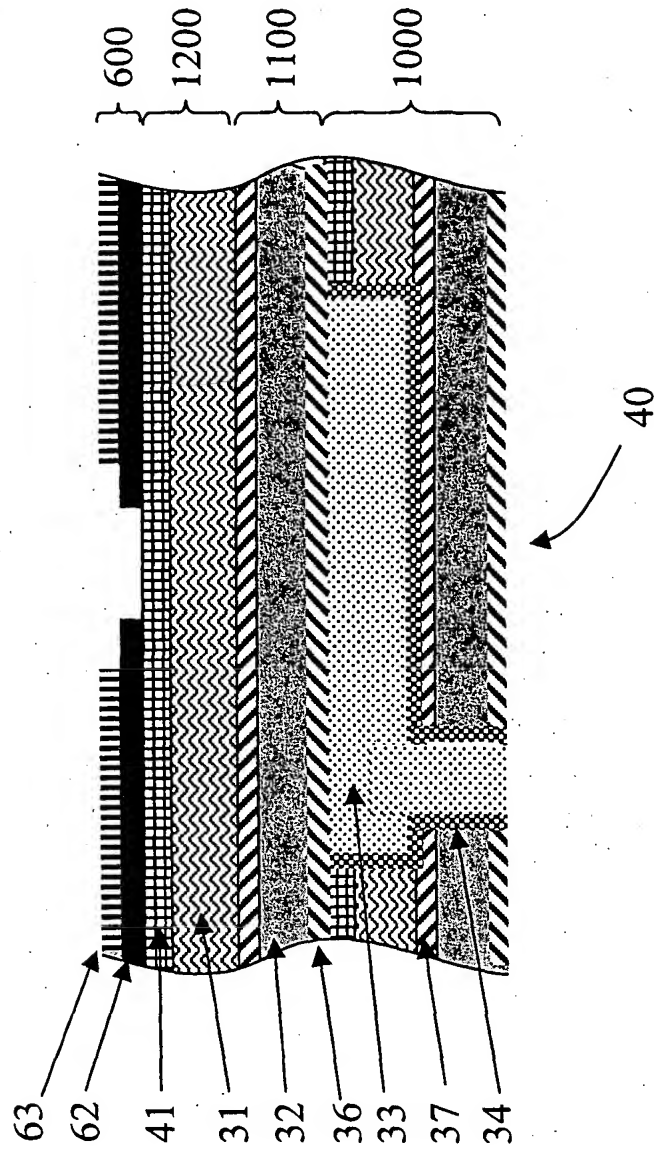


Figure 3: Cross Sectional View of Structure Having a Buried Etch Stop

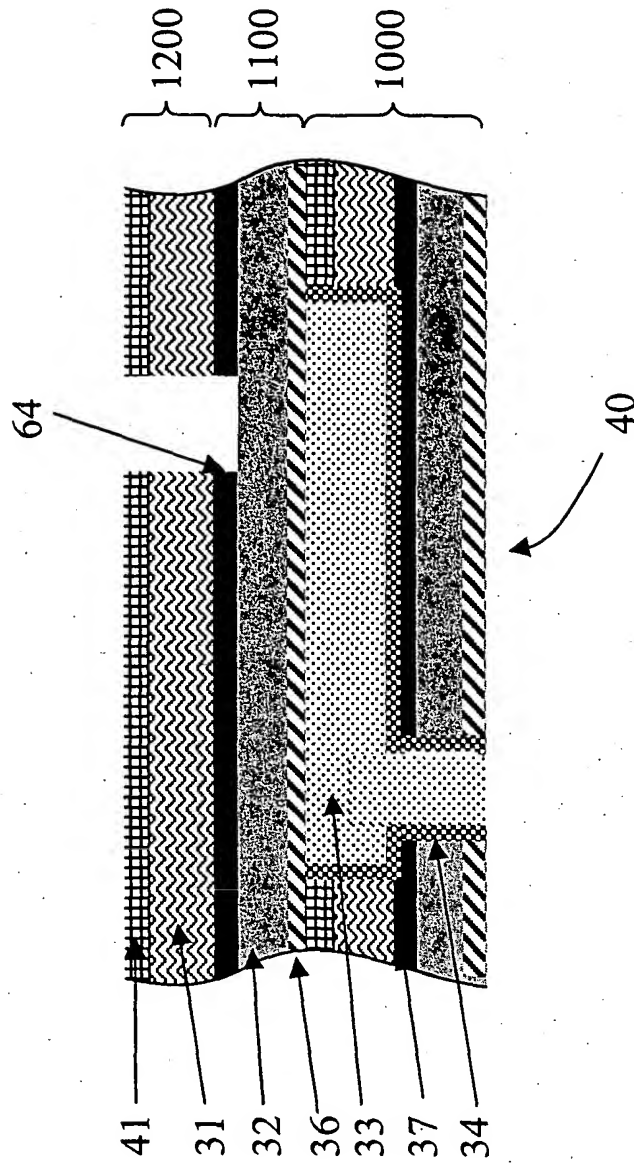


Figure 4: General Process Flow for Generation of Patterned Ceramic Layer

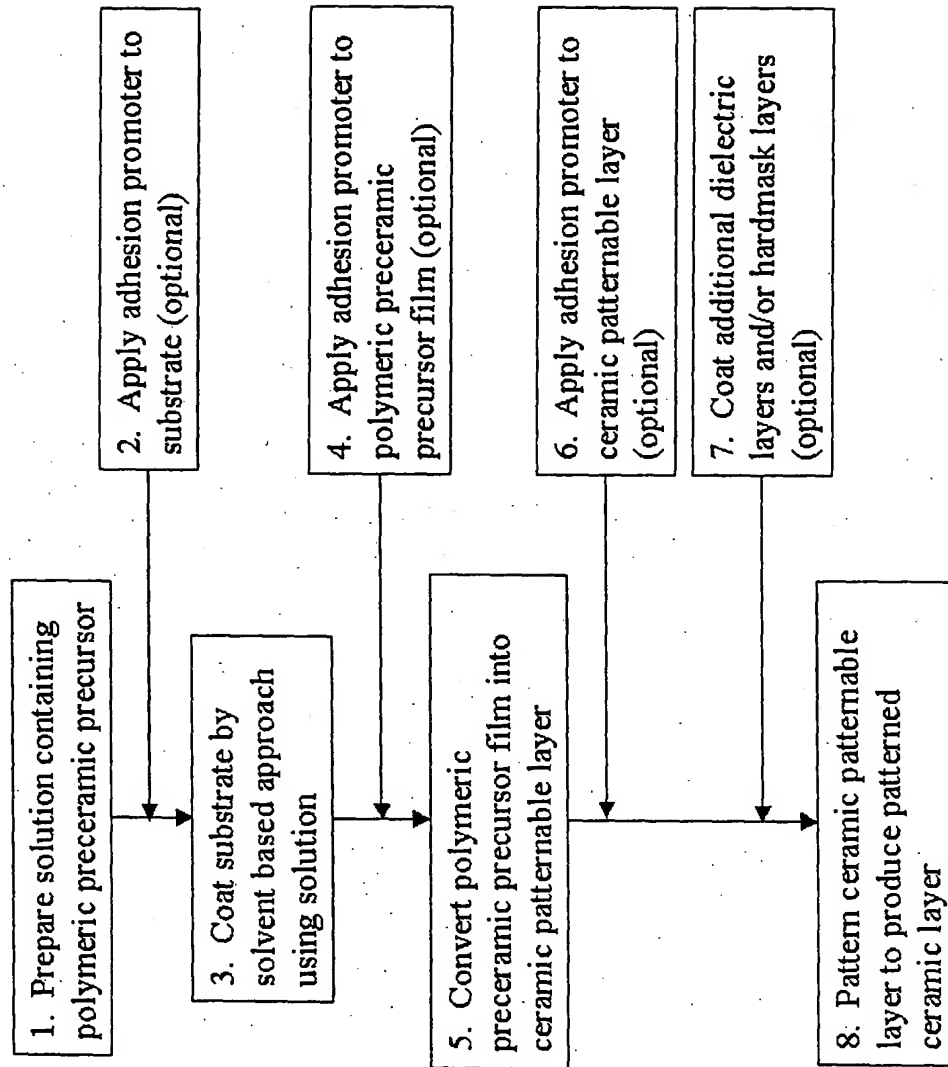


Figure 5: Auger Depth Profiles showing Plasma Resistance Ceramic Patternable Layer Generated from Polysilazane Polymer Preceramic Precursor

